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Future Vision

By K B Hemanth Raj

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Sixth Semester B.E. Degree Examination, June/July 2019

VLSI Design

Time: 3 hrs.

Max. Marks: 80

Note: Answer any **FIVE** full questions, choosing **ONE** full question from each module.

Module-1

- 1 a. Derive the CMOS inverter DC characteristics graphically from p device and n device characteristics and show all operating regions. (08 Marks)
- b. Explain the working of nMOS enhancement mode transistor with suitable diagrams. (08 Marks)

OR

- 2 a. Derive expression for drain current in linear and saturation region for nMOS transistor. (08 Marks)
- b. With neat sketches explain the CMOS P-well process steps to fabricate a CMOS inverter. (08 Marks)

Module-2

- 3 a. Write the lambda based design rules for separation of layers and transistors. (06 Marks)
- b. Draw circuit, stick and layout diagram for nMOS shift register cell. (10 Marks)

OR

- 4 a. Define sheet resistance (R_s) standard unit of capacitance ($\square C_g$) and delay unit (τ) (06 Marks)
- b. Calculate the capacitance of the structure given below in Fig.Q4(b). (10 Marks)

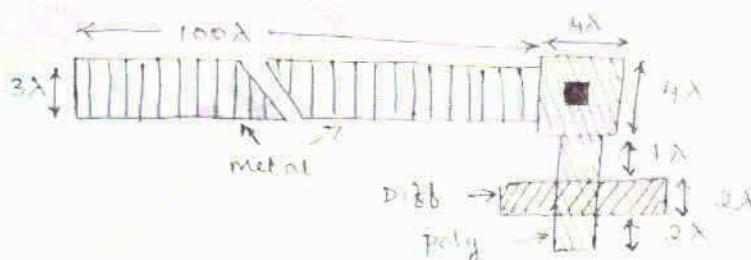


Fig.Q4(b)

Area capacitance value for metal 1 to substrate = $0.3 \text{ pF} \times 10^{-4}/\mu\text{m}^2$ (0.075 relative value)

Area capacitance value for diffusion to substrate = $1 \text{ pF} \times 10^{-4}/\mu\text{m}^2$ (0.25 relative value)

Area capacitance value for polysilicon to substrate = $0.4 \text{ pF} \times 10^{-4}/\mu\text{m}^2$ (0.1 relative value).

Module-3

- 5 a. Obtain the scaling factor for the following device parameters :
 i) gate capacitance
 ii) gate area
 iii) saturation current (I_{dss})
 iv) channel resistance (R_{on})
 v) maximum operating frequency (f_0)
 vi) power dissipation per gate (P_g)
 vii) current density (J)
 viii) gate delay (T_d). (08 Marks)
 b. With a neat diagram explain 4×4 Barrel shifter. (08 Marks)

OR

- 6 a. Explain the general arrangement of a 4 bit data path for processor. (08 marks)
 b. Describe Manchester carry chain element. (08 Marks)

Module-4

- 7 a. Discuss the architectural issues to be followed in the design of VLSI sub system. (05 Marks)
 b. Explain in detail the general structure of an FPGA fabric. (06 Marks)
 c. Explain switch logic implementation of CMOS 5 way selector with neat circuit diagram. (05 Marks)

OR

- 8 a. Explain the structured design approach for the implementation of a parity generator. (08 marks)
 b. Explain dynamic CMOS logic with example. (08 Marks)

Module-5

- 9 a. Explain 3 transistor dynamic RAM cell with schematic diagram. (06 Marks)
 b. Explain any two fault models in combinational circuits. (06 Marks)
 c. Write a note on automatic test pattern generation. (04 Marks)

OR

- 10 a. write short notes on :
 i) observability and controllability
 ii) Built In Self Test (BIST). (08 Marks)
 b. Explain nMOS pseudo static RAM cell with schematic diagram. (08 Marks)

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